

## SEM and E-Beam Lithography

- ZrO/W Schottky Emission Electron Gun
- SE Resolution:
  - 1.2nm (@ 30kV, WD=5mm, Mag. 180kx)
  - 3.0nm (@1kV, WD=3mm, Mag. 80kx)
  - 2.0nm (@1kV, WD=3mm, Mag. 120kx) with Beam Deceleration
- BSE Resolution: 3.0nm (@15kV, WD=5mm, VP 10Pa)
- Variable Pressure mode capability
- Intuitive Auto Startup Feature (HV on, focus, brightness and contrast)
- Automated Optical Axis Alignment and Astigmatism Correction Mode
- Large Variable Pressure Range: 10-300Pa
- Accommodates up to 4" Diameter Specimens (Max. 55 mm height)
- 200nA of Beam Current in both HV and VP Modes
- Interfaced with NPGS for E-beam lithography

